L	Hits	Search Text	DB	Time stamp
Number 1	372378	<pre>(mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1)</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/20 07:49
2	99250	<pre>((mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1)) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4))</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/20 07:56
3	380140	"3" and ((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/20 07:54
4	17743	<pre>(((mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1)) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4))) and ((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$4))</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/20 07:56
5	611	<pre>((((mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1)) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4))) and ((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$4))) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/20 07:57
6	50	(((((mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1)) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4))) and ((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$4))) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1)) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/20 07:59

<u> </u>	7	111111111111111111111111111111111111111	Lugnam	1 2004 /01 /02
7		<pre>(((((mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1)) and ((mask\$4 or pattern\$4) same</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/20 07:59
		(photosensitive or layer\$1 or resist\$1))	DERWENT	
		and ((workpiece\$1 or substrate\$1) same		
		(support\$4 or align\$4 or stage\$4 or mov\$4		
		or rotat\$4))) and ((ink\$1 or liquid\$1 or		
		fluid\$1) same (deposit\$4 or eject\$4 or		
		jet\$4 or drop\$4 or droplet\$4))) and		
		((mask\$4 or pattern\$4) same		
		(photosensitive or layer\$1 or resist\$1))		
		and ((workpiece\$1 or substrate\$1) same		
		<pre>(stage\$4 and mov\$4 and rotat\$4))) and (((mask\$4 or pattern\$4) same (negative</pre>		
		with (photosensitive or layer\$1 or		
		resist\$1))) and ((workpiece\$1 or		
		substrate\$1) same (stage\$4 and mov\$4 and		
ļ		rotat\$4)) same ((ink\$1 or liquid\$1 or		
		fluid\$1) same (deposit\$4 or eject\$4 or		
		<pre>jet\$4 or drop\$4 or droplet\$4)))</pre>		
8	17	((((((mask\$4 or pattern\$4) and	USPAT;	2004/01/20
1		(photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1)) and	US-PGPUB; EPO; JPO;	08:08
		((mask\$4 or pattern\$4) same	DERWENT	
		(photosensitive or layer\$1 or resist\$1))	DEKMENT	
		and ((workpiece\$1 or substrate\$1) same		
		(support\$4 or align\$4 or stage\$4 or mov\$4		
		or rotat\$4))) and ((ink\$1 or liquid\$1 or		
-		fluid\$1) same (deposit\$4 or eject\$4 or		
		jet\$4 or drop\$4 or droplet\$4))) and		
		<pre>((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1))</pre>		
		and ((workpiece\$1 or substrate\$1) same		
		(stage\$4 and mov\$4 and rotat\$4))) and		
		((mask\$4 or pattern\$4) same (negative		
		with (photosensitive or layer\$1 or		
		resist\$1))) and ((workpiece\$1 or		
		substrate\$1) same (stage\$4 and mov\$4 and		
11	4	rotat\$4))) and lithography (((((((mask\$4 or pattern\$4) and	USPAT;	2004/01/20
		(photosensitive or layer\$1 or resist\$1)	US-PGPUB;	08:07
		and (workpiece\$1 or substrate\$1)) and	EPO; JPO;	
		((mask\$4 or pattern\$4) same	DERWENT	
		(photosensitive or layer\$1 or resist\$1))		
		and ((workpiece\$1 or substrate\$1) same		
		(support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4))) and ((ink\$1 or liquid\$1 or		
		fluid\$1) same (deposit\$4 or eject\$4 or		
		jet\$4 or drop\$4 or droplet\$4))) and		
		((mask\$4 or pattern\$4) same		
		(photosensitive or layer\$1 or resist\$1))		
		and ((workpiece\$1 or substrate\$1) same		
		(stage\$4 and mov\$4 and rotat\$4))) and		}
		((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or		
		resist\$1))) and ((workpiece\$1 or		
		substrate\$1) same (stage\$4 and mov\$4 and		
		rotat\$4))) and lithography) and		
	<u> </u>	430/\$.ccls.		

1.0	T	1//////	Transm.	10004/01/00
12	1	((((((mask\$4 or pattern\$4) and	USPAT;	2004/01/20
		(photosensitive or layer\$1 or resist\$1)	US-PGPUB;	08:07
		and (workpiece\$1 or substrate\$1)) and	EPO; JPO;]
		((mask\$4 or pattern\$4) same	DERWENT	
		(photosensitive or layer\$1 or resist\$1))		
		and ((workpiece\$1 or substrate\$1) same		
	1	(support\$4 or align\$4 or stage\$4 or mov\$4		
		or rotat\$4))) and ((ink\$1 or liquid\$1 or		
		fluid\$1) same (deposit\$4 or eject\$4 or		
		jet\$4 or drop\$4 or droplet\$4))) and		
		((mask\$4 or pattern\$4) same		
		(photosensitive or layer\$1 or resist\$1))		
		and ((workpiece\$1 or substrate\$1) same	į	
		(stage\$4 and mov\$4 and rotat\$4))) and		
		((mask\$4 or pattern\$4) same (negative		
		with (photosensitive or layer\$1 or		
		resist\$1))) and ((workpiece\$1 or		
		substrate\$1) same (stage\$4 and mov\$4 and		
İ		rotat\$4))) and lithography) and		
] .			
12	. 12	427/\$.ccls.	HCDATT -	2004/01/20
13	13	(((((((mask\$4 or pattern\$4) and	USPAT;	2004/01/20
		(photosensitive or layer\$1 or resist\$1)	US-PGPUB;	08:10
		and (workpiece\$1 or substrate\$1)) and	EPO; JPO;	
		((mask\$4 or pattern\$4) same	DERWENT	
		(photosensitive or layer\$1 or resist\$1))		
		and ((workpiece\$1 or substrate\$1) same		
		(support\$4 or align\$4 or stage\$4 or mov\$4		
		or rotat\$4))) and ((ink\$1 or liquid\$1 or		ļ
		fluid\$1) same (deposit\$4 or eject\$4 or		
		jet\$4 or drop\$4 or droplet\$4))) and	}	1
		((mask\$4 or pattern\$4) same		
		<pre>(photosensitive or layer\$1 or resist\$1))</pre>		
		and ((workpiece\$1 or substrate\$1) same		
		(stage\$4 and mov\$4 and rotat\$4))) and		
		((mask\$4 or pattern\$4) same (negative		
		with (photosensitive or layer\$1 or		'
		resist\$1))) and ((workpiece\$1 or		
		substrate\$1) same (stage\$4 and mov\$4 and		
		rotat\$4))) and lithography) not		
		(((((((mask\$4 or pattern\$4) and		
	1	(photosensitive or layer\$1 or resist\$1)		
		and (workpiece\$1 or substrate\$1)) and		
I		((mask\$4 or pattern\$4) same		
		<pre>(photosensitive or layer\$1 or resist\$1))</pre>		
		and ((workpiece\$1 or substrate\$1) same		
		(support\$4 or align\$4 or stage\$4 or mov\$4		
		or rotat\$4))) and ((ink\$1 or liquid\$1 or		
		fluid\$1) same (deposit\$4 or eject\$4 or]
		<pre>jet\$4 or drop\$4 or droplet\$4))) and</pre>		
		((mask\$4 or pattern\$4) same		
		<pre>(photosensitive or layer\$1 or resist\$1))</pre>		
		and ((workpiece\$1 or substrate\$1) same		
		(stage\$4 and mov\$4 and rotat\$4))) and		
		((mask\$4 or pattern\$4) same (negative		
		with (photosensitive or layer\$1 or		
		resist\$1))) and ((workpiece\$1 or]
		substrate\$1) same (stage\$4 and mov\$4 and		
		rotat\$4))) and lithography) and		
		430/\$.ccls.)		
		450/9.CCIS.)		L

		T 444	1 0 0 0 1 0 0 1 0 0
14 33	<pre>(((((((mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1)) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4))) and ((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$4))) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1))) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) not (((((((mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1) and ((mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and ((mask\$4 or pattern\$4) same (stage\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4))) and ((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/20 08:31
20 561	(stage\$4 and mov\$4 and rotat\$4))) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1))) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) not ((((((mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1)) and ((mask\$4 or pattern\$4)) same (photosensitive or layer\$1 or resist\$1)) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1)) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4))) and ((ink\$1 or liquid\$1 or fluid\$1) same	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/20 08:34
	((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1))		
	-and -((workpiece\$1 or substrate\$1-) same (stage\$4 and mov\$4 and rotat\$4))) and		
	((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or		
	resist\$1))) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and		
	rotat\$4)))		

21	31	(((((mask\$4 or pattern\$4) and	USPAT;	2004/01/20	Ī
		(photosensitive or layer\$1 or resist\$1)	US-PGPUB;	08:40	l
		and (workpiece\$1 or substrate\$1)) and	EPO; JPO;		l
		((mask\$4 or pattern\$4) same	DERWENT		l
		(photosensitive or layer\$1 or resist\$1))			l
l		and ((workpiece\$1 or substrate\$1) same			l
I		(support\$4 or align\$4 or stage\$4 or mov\$4			١
İ		or rotat\$4))) and ((ink\$1 or liquid\$1 or			l
İ		fluid\$1) same (deposit\$4 or eject\$4 or			ı
Ì		jet\$4 or drop\$4 or droplet\$4))) and			۱
		((mask\$4 or pattern\$4) same			
1		(photosensitive or layer\$1 or resist\$1))			
	ļ	and ((workpiece\$1 or substrate\$1) same			
		(stage\$4 and mov\$4 and rotat\$4))) not			
		((((((mask\$4 or pattern\$4) and			
	1	(photosensitive or layer\$1 or resist\$1)			
		and (workpiece\$1 or substrate\$1)) and			
ĺ		((mask\$4 or pattern\$4) same	1		
		(photosensitive or layer\$1 or resist\$1))			
		and ((workpiece\$1 or substrate\$1) same			l
		(support\$4 or align\$4 or stage\$4 or mov\$4			1
		or rotat\$4))) and ((ink\$1 or liquid\$1 or			l
		fluid\$1) same (deposit\$4 or eject\$4 or			l
		jet\$4 or drop\$4 or droplet\$4))) and			l
		((mask\$4 or pattern\$4) same			l
	-	(photosensitive or layer\$1 or resist\$1))			ı
		and ((workpiece\$1 or substrate\$1) same			l
		(stage\$4 and mov\$4 and rotat\$4))) and			ı
		((mask\$4 or pattern\$4) same (negative		i	l
		with (photosensitive or layer\$1 or]	1
		resist\$1))) and ((workpiece\$1 or			1
		substrate\$1) same (stage\$4 and mov\$4 and			١
	I	rotat\$4)))) and 347/\$.ccls.	I	1	1

22	530	((((((mask\$4 or pattern\$4) and	USPAT;	2004/01/20
22	330	(photosensitive or layer\$1 or resist\$1)	US-PGPUB;	08:40
		and (workpiece\$1 or substrate\$1)) and	EPO; JPO;	
		((mask\$4 or pattern\$4) same	DERWENT	
		(photosensitive or layer\$1 or resist\$1))		
		and ((workpiece\$1 or substrate\$1) same		
		(support\$4 or align\$4 or stage\$4 or mov\$4		
		or rotat\$4))) and ((ink\$1 or liquid\$1 or		1
		fluid\$1) same (deposit\$4 or eject\$4 or		
		jet\$4 or drop\$4 or droplet\$4))) and		
	i	((mask\$4 or pattern\$4) same		
		(photosensitive or layer\$1 or resist\$1))		
		and ((workpiece\$1 or substrate\$1) same		1
		(stage\$4 and mov\$4 and rotat\$4))) not		
		((((((mask\$4 or pattern\$4) and	1	
	1	(photosensitive or layer\$1 or resist\$1)		
		and (workpiece\$1 or substrate\$1)) and		
		((mask\$4 or pattern\$4) same		
	1	(photosensitive or layer\$1 or resist\$1))		
		and ((workpiece\$1 or substrate\$1) same (support\$4 or align\$4 or stage\$4 or mov\$4		
	[or rotat\$4))) and ((ink\$1 or liquid\$1 or		
		fluid\$1) same (deposit\$4 or eject\$4 or		
		jet\$4 or drop\$4 or droplet\$4))) and		
		((mask\$4 or pattern\$4) same		
		(photosensitive or layer\$1 or resist\$1))		
		and ((workpiece\$1 or substrate\$1) same		
		(stage\$4 and mov\$4 and rotat\$4))) and		
		((mask\$4 or pattern\$4) same (negative		
		with (photosensitive or layer\$1 or		
		resist\$1))) and ((workpiece\$1 or		
İ		substrate\$1) same (stage\$4 and mov\$4 and		
		rotat\$4)))) not ((((((mask\$4 or		
		pattern\$4) and (photosensitive or layer\$1		
		or resist\$1) and (workpiece\$1 or		
		substrate\$1)) and ((mask\$4 or pattern\$4)		
		same (photosensitive or layer\$1 or		
		resist\$1)) and ((workpiece\$1 or		
		substrate\$1) same (support\$4 or align\$4		
		or stage\$4 or mov\$4 or rotat\$4))) and		·
		((ink\$1 or liquid\$1 or fluid\$1) same		
		(deposit\$4 or eject\$4 or jet\$4 or drop\$4		
		or droplet\$4))) and ((mask\$4 or		
		<pre>pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1</pre>		
		or substrate\$1) same (stage\$4 and mov\$4		
		and rotat\$4))) not (((((mask\$4 or		
		pattern\$4) and (photosensitive or layer\$1		
		or resist\$1) and (workpiece\$1 or		
		substrate\$1)) and ((mask\$4 or pattern\$4)		
		same (photosensitive or layer\$1 or		
	1	resist\$1)) and ((workpiece\$1 or		
		substrate\$1) same (support\$4 or align\$4		
		or stage\$4 or mov\$4 or rotat\$4))) and		
		((ink\$1 or liquid\$1 or fluid\$1) same		
		(deposit\$4 or eject\$4 or jet\$4 or drop\$4		
	1	or droplet\$4))) and ((mask\$4 or		
		pattern\$4) same (photosensitive or		
		layer\$1 or resist\$1)) and ((workpiece\$1		
		or substrate\$1) same (stage\$4 and mov\$4		
		and rotat\$4))) and ((mask\$4 or pattern\$4)		
		same (negative with (photosensitive or		
		layer\$1 or resist\$1))) and ((workpiece\$1		
	-	or substrate\$1) same (stage\$4 and mov\$4		
L	l	and rotat\$4)))) and 347/\$.ccls.)		_1

23	87	(((((((mask\$4 or pattern\$4) and	USPAT;	2004/01/20
2.5) ,	(photosensitive or layer\$1 or resist\$1)	US-PGPUB;	08:48
				00.10
		and (workpiece\$1 or substrate\$1)) and	EPO; JPO;	
		((mask\$4 or pattern\$4) same	DERWENT	
		(photosensitive or layer\$1 or resist\$1))		
		and ((workpiece\$1 or substrate\$1) same		
		(support\$4 or align\$4 or stage\$4 or mov\$4		
		or rotat\$4))) and ((ink\$1 or liquid\$1 or		
		fluid\$1) same (deposit\$4 or eject\$4 or		
		jet\$4 or drop\$4 or droplet\$4))) and		
		((mask\$4 or pattern\$4) same		
		(photosensitive or layer\$1 or resist\$1))		
		and ((workpiece\$1 or substrate\$1) same		
		(stage\$4 and mov\$4 and rotat\$4))) not		
1		((((((mask\$4 or pattern\$4) and		
ļ		(photosensitive or layer\$1 or resist\$1)		
		and (workpiece\$1 or substrate\$1)) and		
i		((mask\$4 or pattern\$4) same		
1		(photosensitive or layer\$1 or resist\$1))		
i		1 **		
		and ((workpiece\$1 or substrate\$1) same		
		(support\$4 or align\$4 or stage\$4 or mov\$4		
		or rotat\$4))) and ((ink\$1 or liquid\$1 or		1
		fluid\$1) same (deposit\$4 or eject\$4 or		j i
		jet\$4 or drop\$4 or droplet\$4))) and		1
		((mask\$4 or pattern\$4) same		1
		(photosensitive or layer\$1 or resist\$1))		
		and ((workpiece\$1 or substrate\$1) same		
		(stage\$4 and mov\$4 and rotat\$4))) and		1
				i
		((mask\$4 or pattern\$4) same (negative		
	ł	with (photosensitive or layer\$1 or		
		resist\$1))) and ((workpiece\$1 or		
		substrate\$1) same (stage\$4 and mov\$4 and		
		rotat\$4)))) not ((((((mask\$4 or		
		pattern\$4) and (photosensitive or layer\$1		
		or resist\$1) and (workpiece\$1 or		
		substrate\$1)) and ((mask\$4 or pattern\$4)		
		same (photosensitive or layer\$1 or		
		1		
		resist\$1)) and ((workpiece\$1 or		
		substrate\$1) same (support\$4 or align\$4		
		or stage\$4 or mov\$4 or rotat\$4))) and		l
		((ink\$1 or liquid\$1 or fluid\$1) same		
		(deposit\$4 or eject\$4 or jet\$4 or drop\$4		
		or droplet\$4))) and ((mask\$4 or		
		pattern\$4) same (photosensitive or		
		layer\$1 or resist\$1)) and ((workpiece\$1		
1		or substrate\$1) same (stage\$4 and mov\$4		
		and rotat\$4))) not (((((mask\$4 or		
ĺ		pattern\$4) and (photosensitive or layer\$1		
		paccetingly and (phocosensticive of layers)		
		or resist\$1) and (workpiece\$1 or		
		substrate\$1)) and ((mask\$4 or pattern\$4)		
		same (photosensitive or layer\$1 or		
		resist\$1)) and ((workpiece\$1 or		
		substrate\$1) same (support\$4 or align\$4		
		or stage\$4 or mov\$4 or rotat\$4))) and		
		((ink\$1 or liquid\$1 or fluid\$1) same		
		(deposit\$4 or eject\$4 or jet\$4 or drop\$4		
	l ·	or droplet\$4))) and ((mask\$4 or		
		pattern\$4) same (photosensitive or		
		layer\$1 or resist\$1)) and ((workpiece\$1		
		1	l ,	
		or substrate\$1) same (stage\$4 and mov\$4		
		and rotat\$4))) and ((mask\$4 or pattern\$4)		
		same (negative with (photosensitive or		
		layer\$1 or resist\$1))) and ((workpiece\$1		
-		or substrate\$1) same (stage\$4 and mov\$4		ļ
		and rotat\$4)))) and 347/\$.ccls.)) and		
	Į	427/\$.ccls.	1	
Ц	1	<u> </u>	L	·

24	13	(((((((mask\$4 or pattern\$4) and	USPAT;	2004/01/20
	13	(photosensitive or layer\$1 or resist\$1)	US-PGPUB;	08:48
		and (workpiece\$1 or substrate\$1)) and	EPO; JPO;	
		((mask\$4 or pattern\$4) same	DERWENT	
		(photosensitive or layer\$1 or resist\$1))		
		and ((workpiece\$1 or substrate\$1) same		
		(support\$4 or align\$4 or stage\$4 or mov\$4		
		or rotat\$4))) and ((ink\$1 or liquid\$1 or		
		fluid\$1) same (deposit\$4 or eject\$4 or		
		jet\$4 or drop\$4 or droplet\$4))) and		
		((mask\$4 or pattern\$4) same		
		(photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same		
		(stage\$4 and mov\$4 and rotat\$4))) not		
		((((((mask\$4 or pattern\$4) and		
		(photosensitive or layer\$1 or resist\$1)		ĺ
		and (workpiece\$1 or substrate\$1)) and		
		((mask\$4 or pattern\$4) same		l i
		(photosensitive or layer\$1 or resist\$1))		1
		and ((workpiece\$1 or substrate\$1) same		
		(support\$4 or align\$4 or stage\$4 or mov\$4		ĺ
		or rotat\$4))) and ((ink\$1 or liquid\$1 or		
ŀ		fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$4))) and		
		((mask\$4 or pattern\$4) same		
		(photosensitive or layer\$1 or resist\$1))		
		and ((workpiece\$1 or substrate\$1) same		
		(stage\$4 and mov\$4 and rotat\$4))) and		
		((mask\$4 or pattern\$4) same (negative		
		with (photosensitive or layer\$1 or		·
		resist\$1))) and ((workpiece\$1 or		
		substrate\$1) same (stage\$4 and mov\$4 and		1
		rotat\$4)))) not ((((((mask\$4 or		
		pattern\$4) and (photosensitive or layer\$1		
		or resist\$1) and (workpiece\$1 or substrate\$1)) and ((mask\$4 or pattern\$4)		
		same (photosensitive or layer\$1 or		
		resist\$1)) and ((workpiece\$1 or		
		substrate\$1) same (support\$4 or align\$4		
		or stage\$4 or mov\$4 or rotat\$4))) and		
		((ink\$1 or liquid\$1 or fluid\$1) same		
		(deposit\$4 or eject\$4 or jet\$4 or drop\$4		
		or droplet\$4))) and ((mask\$4 or		
		pattern\$4) same (photosensitive or		
		layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4		
		and rotat\$4))) not (((((mask\$4 or		
		pattern\$4) and (photosensitive or layer\$1		
		or resist\$1) and (workpiece\$1 or		
		substrate\$1)) and ((mask\$4 or pattern\$4)		
		same (photosensitive or layer\$1 or		
		resist\$1)) and ((workpiece\$1 or		
		substrate\$1) same (support\$4 or align\$4		
		or stage\$4 or mov\$4 or rotat\$4))) and ((ink\$1 or liquid\$1 or fluid\$1) same		
		(deposit\$4 or eject\$4 or jet\$4 or drop\$4		
		or droplet\$4))) and ((mask\$4 or		
		pattern\$4) same (photosensitive or		
		layer\$1 or resist\$1)) and ((workpiece\$1		
		or substrate\$1) same (stage\$4 and mov\$4		
		and rotat\$4))) and ((mask\$4 or pattern\$4)		
		same (negative with (photosensitive or		
		layer\$1 or resist\$1))) and ((workpiece\$1		
-		or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and 347/\$.ccls.)) and		
		and rotat(\$4)))) and \$47/\$.ccis.)) and 250/\$.ccis.		
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